

then, in which 90 percent of the incident flux is absorbed, is

$$d = \frac{1}{10^4} \ln \left(\frac{1}{0.1} \right) = 2.30 \times 10^{-4} \text{ cm} = 2.30 \text{ } \mu\text{m}$$

■ Comment

As the incident photon energy increases, the absorption coefficient increases rapidly so that the photon energy can be totally absorbed in a very narrow region at the surface of a semiconductor.

■ EXERCISE PROBLEM

Ex 14.1 Consider a slab of silicon $5 \text{ } \mu\text{m}$ thick. Determine the percentage of photons that will pass through the slab if the photon wavelength is (a) $\lambda = 0.8 \text{ } \mu\text{m}$ and (b) $\lambda = 0.6 \text{ } \mu\text{m}$.
[5% (a) 1% (b) 0%]

The relation between the bandgap energies of some of the common semiconductor materials and the light spectrum is shown in Figure 14.5. We may note that silicon and gallium arsenide will absorb all of the visible spectrum, whereas gallium phosphide, for example, will be transparent to the red spectrum.

14.1.2 Electron-Hole Pair Generation Rate

We have shown that photons with energy greater than E_g can be absorbed in a semiconductor, thereby creating electron-hole pairs. The intensity $I_0(x)$ is in units of

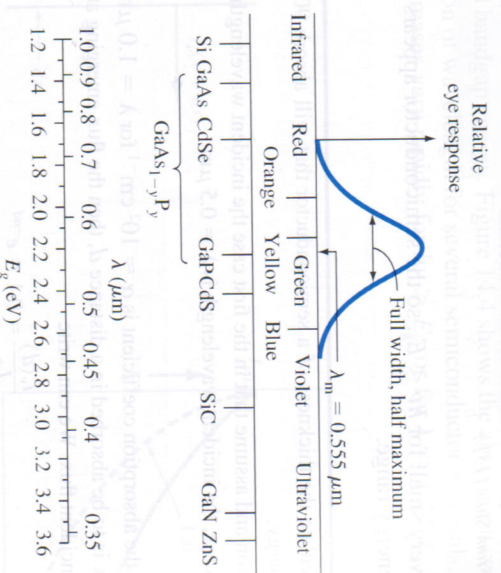


Figure 14.5 Light spectrum versus wavelength and energy. Figure includes relative response of the human eye. (From Sec 118/1)

that one absorbed photon creates one electron-hole pair. The generation rate of electron-hole pairs is

$$g' = \frac{\alpha I_0(x)}{h\nu} \quad (14.6)$$

It is in units of $\#/\text{cm}^3\text{-s}$. We may note that the ratio $I_0(x)/h\nu$ is the photon flux. If, on the average, one absorbed photon produces less than one electron-hole pair, the generation rate (14.6) must be multiplied by an efficiency factor.

Example: Calculate the generation rate of electron-hole pairs given an incident intensity of 0.05 W/cm^2 at a wavelength of $\lambda = 0.75 \text{ } \mu\text{m}$. This intensity is typical of sunlight.

Solution Consider gallium arsenide at $T = 300 \text{ K}$. Assume the photon intensity at a particular wavelength is $I_0(x) = 0.05 \text{ W/cm}^2$ at a wavelength of $\lambda = 0.75 \text{ } \mu\text{m}$. This intensity is typical of sunlight. For example,

$$E = h\nu = \frac{1.24}{0.75} = 1.65 \text{ eV}$$

from Equation (14.6) and including the conversion factor between joules and eV, we have, for a unity efficiency factor,

$$g' = \frac{\alpha I_0(x)}{h\nu} = \frac{(0.9 \times 10^4)(0.05)}{(1.6 \times 10^{-19})(1.65)} = 1.70 \times 10^{21} \text{ cm}^{-3}\text{-s}^{-1}$$

If the incident photon intensity is a steady-state intensity, then, from Chapter 6, the steady-state carrier concentration is $\delta n = g'\tau$, where τ is the excess minority carrier lifetime. If $\tau = 10^{-7} \text{ s}$, for example, then

$$\delta n = (1.70 \times 10^{21})(10^{-7}) = 1.70 \times 10^{14} \text{ cm}^{-3}$$

■ Comment This example gives an indication of the magnitude of the electron-hole generation rate. Obviously, as the photon intensity increases, the generation rate also decreases.

■ EXERCISE PROBLEM

Ex 14.2 A photon flux with an intensity of $I_0 = 0.10 \text{ W/cm}^2$ and at a wavelength of $\lambda = 1 \text{ } \mu\text{m}$ is incident on the surface of silicon. Neglecting any reflection at the surface, determine the generation rate of electron-hole pairs at a depth of (a) $x = 5 \text{ } \mu\text{m}$ and (b) $x = 20 \text{ } \mu\text{m}$ from the surface.
[1.8 $\times 10^{21} \text{ cm}^{-3}\text{-s}^{-1}$ (a) 1.8 $\times 10^{21} \text{ cm}^{-3}\text{-s}^{-1}$ (b) 6.2 $\times 10^{20} \text{ cm}^{-3}\text{-s}^{-1}$]